

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: James W. Blatchford, Jr., et al.
Serial No. Unknown
Filing Date: July 8, 2003
Title: GENERATING AN OPTICAL MODEL FOR LENS
ABERRATIONS

Mail Stop Patent Application

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INFORMATION DISCLOSURE STATEMENT

Applicants respectfully request, pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, that the references listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified patent application. Copies of these references are enclosed for the convenience of the Examiner. No representation is made that a search has been made, that these references qualify as prior art or that these references are material to the patentability of the present application.

Respectfully submitted,

Baker Botts L.L.P.
Attorneys for Applicant

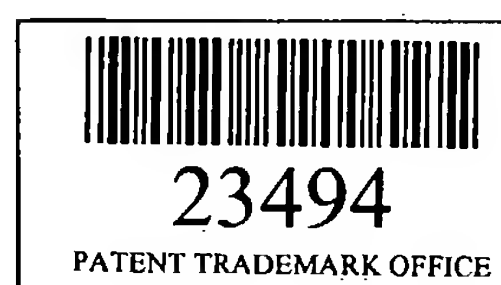


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Date: July 8, 2003

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PTO-1449 Information Disclosure Citation In an Application	Application No. Unknown		Applicant(s) James W. Blatchford, Jr., et al.	
	Docket Number TI-35516 (032350.B504)	Group Art Unit Unknown	Filing Date July 8, 2003	

U.S. PATENT DOCUMENTS

		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						
	J						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	K							
	L							
	M							
	N							

		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
	O	FringeSoft, Zernike and Seidel Polynomials, Zernike polynomials, http://www.fringesoft.com/siedel.htm ; copyright 2000 FringeSoft; 2 pages.	June 28, 2000
	P	Gennari, Frank E., "Validation of the aberration pattern-matching OPC strategy," Design, Process Integration, and Characterization for Microelectronics, Alexander Starikov, Kenneth W. Tobin, Jr., Editors, Proceedings of SPIE Vol. 4692, pages 444-453.	2002
	Q	Calibre OPC and PSM, Manufacturability Datasheet, "Calibre OPC and PSM: Enabling Silicon Accuracy, Speed and Yield from 180nm to 65nm," Mentor Graphics, Mentor Graphics Corporation, www.mentor.com/dsm , 6 pages.	April 2003
	R		

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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